

REMARKS

Claims 1-11 and 39-49 are pending in the above-identified application. In the final Office Action dated March 14, 2006, the Examiner made the following disposition:

- A.) Allowed claims 1-11 and 87-89.
- B.) Rejected claim 39 under 37 CFR 1.78(b) as double patenting in view of claim 1 of Serial No. 11/103,809.

Applicants respectfully traverse the rejection and address the Examiner's disposition below.

- A.) Allowance claims 1-11 and 87-89:

Applicants respectfully acknowledge the Examiner's finding of allowable subject matter in claims 1-11 and 87-89.

- B.) Double patenting rejection of claims 39-49 in view of claim 1 of Serial No. 11/103,809:

Applicants respectfully disagree with the rejection.

Independent claim 39 of the present application claims subject matter relating to a *mask*, wherein a supporting region has first alignment marks used at the time of *exposure of the mask* for forming mask circuit patterns thereon, and second alignment marks used at the time of *exposure of a substrate* to be exposed for forming circuit patterns thereon.

This is unlike claim 1 of pending Serial No. 11/103,809, which claims subject matter relating to a *mask-making member*. Applicants note that Serial No. 11/103,809 is currently pending, and thus it is premature to determine whether there is a double patenting rejection based on its claims. Further, Applicants note that an amendment was mail on March 15, 2006 in Serial No. 11/103,809, after the mailing to the March 14, 2006 office action in the present application.

In the amendment mailed on March 15, 2006 in Serial No. 11/103, 809, claim 1 of that application was amended to further differentiate that claim from claim 39 of the present application. Namely, in addition to claim 1 of Serial No. 11/103,809 relating to a *mask-making member*, claim 1 of Serial No. 11/103,809 also claims a supporting region that has first alignment marks used at a time of *alignment with a mask made from a mask-making member*, and second alignment marks used at a time of *alignment with a substrate*. This is unlike claim 39 of the present application which claims a *mask*, wherein a supporting region has first alignment marks used at the time of *exposure of the mask* for forming mask circuit patterns thereon, and second alignment marks used at the time of *exposure of a substrate* to be exposed for forming circuit patterns thereon.

Therefore, Applicants respectfully submit that there is no double patenting of claim 39 of the present application in view of claim 1 of Serial No. 11/103,809.

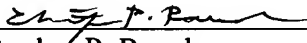
Claims 40-49 depend directly or indirectly from claim 39 and are therefore allowable for at least the same reasons that claim 39 is allowable.

Applicants respectfully submit the rejection has been overcome and request that it be withdrawn.

In view of the foregoing, Applicants submit that the application is in condition for allowance. Notice to that effect is requested.

Respectfully submitted,

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